

# Hisashi Ohsaki

## List of Publications by Year in descending order

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47  
papers

800  
citations

516561

16  
h-index

526166

27  
g-index

47  
all docs

47  
docs citations

47  
times ranked

829  
citing authors

| #  | ARTICLE  | IF  | CITATIONS |
|----|--|-----|-----------|
| 1  | Fabrication of Mo microcones for volcano-structured double-gate Spindt-type emitter cathodes using triode high power pulsed magnetron sputtering. Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2017, 35, . | 0.6 | 7         |
| 2  | Crystallization of ITO and TiO <sub>2</sub> by RF plasma treatment. Vacuum, 2013, 87, 145-149.   | 1.6 | 6         |
| 3  | Multilayered Ordering of the Metal Nanoparticles in Polymer Thin Films under Photoirradiation. Langmuir, 2011, 27, 733-740.  | 1.6 | 9         |
| 4  | Densification of spin-on-glass (SOG) film by RF plasma treatment. IOP Conference Series: Materials Science and Engineering, 2011, 18, 032007.  | 0.3 | 0         |
| 5  | Band-selective Mirror Characteristics of Polymer/Metal Multilayer Films. Chemistry Letters, 2011, 40, 1138-1139.   | 0.7 | 3         |
| 6  | Anatase TiO <sub>2</sub> Films Crystallized by RF Plasma Treatment. IOP Conference Series: Materials Science and Engineering, 2011, 18, 172004.  | 0.3 | 1         |
| 7  | Room-temperature crystallization of amorphous films by RF plasma treatment. Thin Solid Films, 2009, 517, 3092-3095.  | 0.8 | 20        |
| 8  | Room temperature crystallization by RF plasma. Thin Solid Films, 2008, 516, 4490-4494.   | 0.8 | 11        |
| 9  | Characterization of sputtered triple layer photoactive coating with a glass-like appearance. Thin Solid Films, 2008, 516, 4558-4562.   | 0.8 | 5         |
| 10 | Room temperature crystallization of indium tin oxide films on glass and polyethylene terephthalate substrates using rf plasma. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2007, 25, 1052-1055.                    | 0.9 | 10        |
| 11 | Preparation of cobalt-titanium dioxide nanocomposite films by combining inverse micelle method and plasma treatment. Materials Letters, 2007, 61, 2173-2177.   | 1.3 | 9         |
| 12 | Sliding Behavior of Water Droplets on Flat Polymer Surface. Journal of the American Chemical Society, 2006, 128, 743-747.  | 6.6 | 61        |
| 13 | Effects of vacuum ultraviolet light illumination and seeding on crystallization of sol-gel-derived titanium dioxide precursor films using plasma treatment. Surface and Coatings Technology, 2006, 201, 3038-3043.                             | 2.2 | 6         |
| 14 | Plasma treatment for crystallization of amorphous thin films. Thin Solid Films, 2006, 502, 63-66.  | 0.8 | 17        |
| 15 | Photocatalytic properties of SnO <sub>2</sub> /TiO <sub>2</sub> multilayers. Thin Solid Films, 2006, 502, 138-142.   | 0.8 | 44        |
| 16 | Super-hydrophobic photocatalytic coatings utilizing apatite-based photocatalyst. Thin Solid Films, 2006, 502, 108-111.   | 0.8 | 57        |
| 17 | The underlayer effects on the electrical resistivity of Ag thin film. Thin Solid Films, 2006, 502, 223-227.  | 0.8 | 49        |
| 18 | Preparation of Transparent Thin Film of Novel Apatite-based Photocatalyst. Chemistry Letters, 2005, 34, 1666-1667.   | 0.7 | 9         |

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|----|--|-----|-----------|
| 19 | Preparation and Water Droplet Sliding Properties of Transparent Hydrophobic Polymer Coating by Molecular Design for Self-Organization. Journal of Sol-Gel Science and Technology, 2004, 31, 195-199. | 1.1 | 20        |
| 20 | Optical properties of Ag/dielectric-material multilayers. Vacuum, 2004, 74, 555-559.   | 1.6 | 17        |
| 21 | Photocatalytic efficiency of TiO <sub>2</sub> /SnO <sub>2</sub> thin film stacks prepared by DC magnetron sputtering. Vacuum, 2004, 74, 723-727.   | 1.6 | 52        |
| 22 | Enhancement of photocatalytic activity using UV light trapping effect. Vacuum, 2004, 74, 729-733.  | 1.6 | 14        |
| 23 | Optical properties of multilayers composed of silver and dielectric materials. Thin Solid Films, 2003, 442, 212-216.   | 0.8 | 45        |
| 24 | Low resistance AR stack including silver layer. Thin Solid Films, 2003, 442, 153-157.  | 0.8 | 9         |
| 25 | High rate deposition of TiO <sub>2</sub> by DC sputtering of the TiO <sub>2</sub> target. Thin Solid Films, 2001, 392, 169-173.  | 0.8 | 36        |
| 26 | Title is missing!. Shinku/Journal of the Vacuum Society of Japan, 2001, 44, 520-527.   | 0.2 | 3         |
| 27 | TiO <sub>2</sub> sputter for high rate deposition of TiO <sub>2</sub> . Vacuum, 2000, 59, 836-843.   | 1.6 | 37        |
| 28 | Global market and technology trends on coated glass for architectural, automotive and display applications. Thin Solid Films, 1999, 351, 1-7.  | 0.8 | 59        |
| 29 | High rate sputter deposition of TiO <sub>2</sub> from TiO <sub>2</sub> target. Thin Solid Films, 1999, 351, 57-60.   | 0.8 | 39        |
| 30 | A new layer system of anti-reflective coating for cathode ray tubes. Thin Solid Films, 1999, 351, 235-240.   | 0.8 | 33        |
| 31 | Global market and technology trends on coated glass for architectural, automotive and display applications. , 1999, , 1-7.   |     | 0         |
| 32 | High rate sputter deposition of TiO <sub>2</sub> from TiO <sub>2</sub> target. , 1999, , 85-88.  |     | 0         |
| 33 | Bendable and temperable solar control glass. Journal of Non-Crystalline Solids, 1997, 218, 223-229.  | 1.5 | 5         |
| 34 | High-rate deposition of SiO <sub>2</sub> by modulated DC reactive sputtering in the transition mode without a feedback system. Thin Solid Films, 1996, 281-282, 213-217.                             | 0.8 | 26        |
| 35 | DC reactive sputtering of electro-conductive transparent tin suboxide using a Sn-O <sub>2</sub> /Ar system. Thin Solid Films, 1996, 281-282, 223-227.  | 0.8 | 8         |
| 36 | Materialistic Difference in Macroscopic Friction Coefficients of Sputtered Metal Oxide Thin Films Deposited on Glass. Japanese Journal of Applied Physics, 1996, 35, 1862-1867.                      | 0.8 | 21        |

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|----|--|-----|-----------|
| 37 | Structural analysis of SiO <sub>2</sub> gel films by high energy electron diffraction. Journal of Sol-Gel Science and Technology, 1994, 2, 245-249.  | 1.1 | 14        |
| 38 | Shrinkage of atomic distances in ultrathin a-SiO <sub>2</sub> film. The Philosophical Magazine: Physics of Condensed Matter B, Statistical Mechanics, Electronic, Optical and Magnetic Properties, 1992, 66, 25-36.                      | 0.6 | 7         |
| 39 | Electron Diffraction Analysis of the Structure of SiO <sub>2</sub> Gel-Film. Materials Research Society Symposia Proceedings, 1990, 180, 429.  | 0.1 | 0         |
| 40 | Structural difference of surface and sub-surface native oxides of evaporated amorphous silicon. Journal of Non-Crystalline Solids, 1990, 120, 275-282.   | 1.5 | 0         |
| 41 | Formation mechanism of evaporated a-SiO <sub>2</sub> : An approach from the oxidation processes of a-Si. Applied Surface Science, 1988, 33-34, 773-778.  | 3.1 | 0         |
| 42 | Oxidation mechanism of amorphous silicon in air. Journal of Non-Crystalline Solids, 1987, 93, 395-406.   | 1.5 | 8         |
| 43 | Structure of an extremely thin film of a-SiO <sub>2</sub> . Journal of Non-Crystalline Solids, 1987, 95-96, 1095-1101.   | 1.5 | 7         |
| 44 | Structure of the Natural Oxide of Amorphous Silicon. Japanese Journal of Applied Physics, 1986, 25, 1773-1777.   | 0.8 | 3         |
| 45 | Densimetry of Amorphous Silicon Films by Using a Quartz Oscillator. Japanese Journal of Applied Physics, 1986, 25, 1152-1155.  | 0.8 | 6         |
| 46 | High Energy Electron Diffraction Study on Ionic Character of Amorphous SiO <sub>2</sub> . Japanese Journal of Applied Physics, 1986, 25, 1768-1772.  | 0.8 | 3         |
| 47 | Numerical calculations of elastic scattering amplitudes for high-energy electron scattering by ionized atoms. The Acta Crystallographica Section A, Crystal Physics, Diffractionoretical and General Crystallography, 1980, 36, 316-321. | 0.6 | 4         |